

# IN THE CLAIMS

Kindly amend the claims 1, 2 and 4, and cancel claim 7, so that the claims appear as set forth hereto.

1. (Presently Amended) A method for the manufacture of microstructures (18) in substrates (24), comprising using a combination of photolithographic mask technology and micro contact printing, wherein said microstructure has an aspect ratio in a range of 1:5 to 1:20.
2. (Presently Amended) A method for the manufacture of microstructures in substrates, comprising the steps of
  - a) providing a process mask (10);
  - b) creating soft stamps (16) from a master comprising a microstructure (18) having an aspect ratio in a range of 1:5 to 1:20;
  - c) attaching said soft stamps (16) to said mask (10);
  - d) stamping a desired pattern into a resist layer (26) provided on a substrate (24) to be processed; and
  - e) curing said pattern with UV light.
3. (Original) The method according to claim 2, wherein said mask (10) comprises a plating compensation area.
4. (Presently Amended) The method according to claim 3, wherein said plating compensation area is covered with a metallic layer (12).
5. (Original) The method according to claim 4, wherein said metal is chromium.
6. (Original) The method according to claim 2, wherein said microstructure (18) is mechanically stabilized by greater holding blocks (20, 22) attached to said microstructure (18).

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7. (Cancelled)

8. (Original) A P2 structure for a magnetic recording head, said structure being manufactured according to the method of claim 2.

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